

ABSTRACT

To provide a means for suppressing the rate of dissolution of tungsten while sufficiently removing the impurities remaining on a surface of a polished object to be polished having a layer containing at least tungsten, and tetraethyl orthosilicate or silicon nitride. To provide a composition for surface treatment, which contains a polymer compound having a sulfonic acid (salt) group, at least one compound selected from an amino acid and a polyol, and a dispersing medium, and is used for treating a surface of a polished object to be polished having a layer containing at least tungsten, and tetraethyl orthosilicate or silicon nitride.